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Cranston, RI 02910 (US). **KOCAB, Thomas, J.**; 20
Canob Lane, Wyoming, RI 02898 (US). **HATFIELD,**
John, P.; 139 Spring Street, Hope Valley, RI 02832 (US).

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(74) Agent: **GREELEY, Paul, D.**; Ohlandt, Greeley, Ruggiero
& Perle, L.L.P., One Landmark Square, 10th Floor, Stam-
ford, CT 06901 (US).

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(71) Applicant: **ARCH SPECIALTY CHEMICALS, INC.**
[US/US]; 501 Merritt 7, P.O. Box 4500, Norwalk, CT
06856-4500 (US).

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(72) Inventors: **FERREIRA, Lawrence**; 598 Walnut Street,
Fall River, MA 02720 (US). **BLAKENEY, Andrew, J.**; 30
Brookside Court, Seekonk, MA 02771 (US). **SPAZIANO,**
Gregory, Dominic; 88 Parade Street, Providence, RI
02909 (US). **DIMOV, Ognian**; 56 Sprague Avenue,

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ACTION

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(54) Title: PERFLUOROALKYLSULFONIC ACID COMPOUNDS FOR PHOTORESISTS

(57) Abstract: A photoacid compound having general structure: $R-O(CF_2)_nSO_3X$ wherein n is an integer between about 1 to 4; R is selected from the group consisting of: substituted or unsubstituted C_1 - C_{12} linear or branched alkyl or alkenyl, substituted or unsubstituted aralkyl, substituted or unsubstituted aryl, substituted or unsubstituted bicycloalkyl, substituted or unsubstituted tricycloalkyl, hydrogen, alkyl sulfonic acid, substituted or unsubstituted perfluoroalkyl, the general structure $F((CF_2)_pO)_m(CF_2)_q-$ wherein p is between about 1 to 4, m is between about 0 to 3 and q is between about 1 to 4, and substituted or unsubstituted partially fluorinated alkyl, haloalkyl, perfluoroalkylsulfonic, or glycidyl; and X is selected from the group consisting of: organic cations and covalently bonded organic radicals.